A new approach for absorption enhancement in plasmonic photodetectors
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Abstract- A new structure for absorption enhancement in plasmonic MSM photodetector is presented. This structure contains a layer of SiO$_2$ between gold and semiconductor layers. The SiO$_2$ layer creates a more suitable path for light to penetrate under the metal layer, transmits the wave to both sides of the device, involves a greater part of semiconductor in electron-hole generation, and increases the coupling of light into the semiconductor. This construction is simulated using Lumerical FDTD. Absorption enhancement in this paper is 4 times greater than similar structures.

Keywords: photodetector, surface plasmon polaritons, nanostructures, grating
1 Introduction

High-speed chip-to-chip connections and high-speed sampling are two main properties to make the metal-semiconductor-metal photodetectors (MSM-PDs) attractive for optical fiber communication systems [1, 2]. In the past decade, many experimental and theoretical works have been carried out to analyze Extraordinary Optical Transmission (EOT) through a subwavelength aperture and demonstrate light absorption enhancement through the nano-patterning of the metal fingers of the MSM photodetectors [3-5].

Recently, excitation and propagation of surface plasmonic polaritons (SPPs) along the interface of a metallic-grating and a semiconductor material have been demonstrated using the finite-difference time-domain (FDTD) method [6, 7]. For instance, Bhat et al. presented a theoretical approach for light absorption enhancement of over 100 times, compared to the conventional MSM photodetectors using FDTD-based simulation of a subwavelength-aperture MSM photodetector structure [7]. These theoretical enhancements encouraged the researchers to design and fabricate novel high-speed high-responsivity MSM photodetector structures [8, 9].

In the present paper the initial model is adopted from [10]. Moreover, the optimization of the metal grating simulated in [11] is used. Then, our proposed structure is presented in which a layer of SiO₂ is added to the device. The three different structures are simulated with Numerical FDTD and their light absorption is compared.

The rest of this paper is organized as follows. In Section 2, the previous MSM plasmonic photodetector structures and our proposed design are explained. In Section 3, the results for the absorption coefficient are presented and compared. Finally, we conclude our discussion in Section 4.

2 Structure Design

Tan et al. presented and optimized an MSM plasmonic photodetector structure which consists of three separated parts: the metal grating, the subwavelength aperture and the substrate, as shown in Fig. 1 [11]. The metal grating includes a perfect conductor whose grooves are parallel to the z-direction and the dimensions are optimized in order to couple the light at the desired wavelength and excite SPPs along the x-direction.
Using the semi-analytic Fabry–Perot analysis [10], the modal expansion formalism [12], and the Green’s tensor analysis [13], it is concluded in [11] that with the subwavelength aperture width \((x_d)\) much smaller than the propagating wavelength \((\lambda_0)\), light transmission enhancement and improved absorption in the semiconductor substrate can be obtained. On the other hand, in [14], Sturman et al. modelled the light transmission enhancement through the subwavelength aperture, accurately.

The change of parameters in Fig. 1 leads to change in the transmission of the light into the semiconductor at the desired wavelength. Therefore, the best values for the parameters are optimized in [11].

The proposed design in this paper is shown in Fig. 3 in which the optimized grating dimensions are adopted from [11] and [15] to achieve the best response from the grating part of the photodetector. Also, a SiO\(_2\) layer is added under the metal (Au) contacts. Since SiO\(_2\) is a dielectric and refuses the generated electron-hole pairs in the semiconductor to reach the metal contacts, two metal side walls are added in both sides of the device to collect the carriers. Figs. 3 and 4 show metal (Au) walls and the SiO\(_2\) layer position more clearly, respectively.

The idea of adding a SiO\(_2\) layer at the end of the aperture is obtained from E-plain Tee divider which is used as a divider in microwave [16]. As shown in Fig. 2 in the conventional plasmonic photodetectors the greatest amount of absorption takes place exactly under the aperture, while Fig. 5 shows the travelling of the entered waves toward both sides of the device.

The 100nm height SiO\(_2\) layer makes the waves propagate more easily toward the sides of the device and a greater part of the semiconductor is involved in the light absorption and carrier generation. The expansion of light under the contacts clearly increases the light absorption. Fig. 6 shows the absorption enhancement compared with Fig. 1 structure in which the transmission is enhanced using metal grating, the conventional structure with no grating and the structure with SiO\(_2\) layer without grating.

The absorption pick takes place at 868 nm using 2D simulation of Lumerical FDTD software with 5nm mesh size.
4 Conclusion

In this paper, we proposed a new design for a plasmonic photodetector by adding a SiO$_2$ layer under the metal grating. This layer provides 4 times improvement of the light absorption at 868nm in comparison with the similar structures.

References


